

APPL NUM 10092875	FILING DATE 03/05/2002	CLASS 257.438	SUBCLASS 396	GAU 2841	2829	EXAMINER K.lda
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+ 689

****CONTINUING DATA VERIFIED:**
LAK none 6/18/03

****FOREIGN APPLICATIONS VERIFIED:**
LAK none 6/18/03

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	ATTORNEY DOCKET NO
35 USC 119 conditions met	<input type="checkbox"/> yes <input checked="" type="checkbox"/> no	M122-1798
Verified and Acknowledged Examiner's initials <i>LAK</i>		

TITLE : Etching processes for integrated circuit manufacturing including methods of forming capacitors

U.S. DEPT. OF COMM./PAT. & TM-PTO-435L (Rev. 12-94)

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FILED WITH: ☐ **DISCLOSURE**

(Attached to patent application)